

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:) Atty. Docket No.: TSUK 0005
Tatsuo CHIBA et al.	Ally. Docket No.: 150K 0005
Serial No. 10/018,690))
Filed: December 20, 2001) Group Art Unit: 1756
For: PHOTOSENSITIVE ELEMENT, PHOTOSENSITIVE ELEMENT ROLL, PROCESS FOR THE PREPARATION OF RESIST PATTERN USING THE SAME, RESIST PATTERN, RESIST	Examiner: PECEIVED PECEIVED
PATTERN LAMINATED SUBSTRATE, PROCESS FOR THE PREPARATION OF WIRING PATTERN AND WIRING PATTERN	Date: March 21, 2002

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

BOX: NO FEE

Assistant Commissioner for Patents

Washington, D. C. 20231

Sir:

Supplemental to the Information Disclosure Statement filed with the application on December 20, 2001, attached is a copy of the International Preliminary Examination Report, which issued on September 21, 2001 in the corresponding international application. All of the documents discussed in the Preliminary Examination Report were cited in applicants' previous Information Disclosure Statement. Accordingly, no further comment in regard to the disclosures of the documents is believed to be required.

It is believed that the present Supplemental Information Disclosure Statement complies with the requirements of 37 C.F.R. §§ 1.97-8, but if a fee should be required, authorization is hereby given to deduct from Deposit Account No. 50-1281.

Respectfully submitted,

GRIFFIN & SZIPL, PC

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